

Correction to "Conformal Organic-Inorganic Hybrid Network Polymer Thin Films by Molecular Layer Deposition using Trimethylaluminum and Glycidol" [The Journal of Physical Chemistry B 2011, 115, 5930–5938. DOI: 10.1021/jp201186k]. Bo Gong, Qing Peng, and Gregory N. Parsons*

The Acknowledgment should read as follows.

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